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## CORRECTION

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## Correction: A facile strategy to realize a single/double photon excitation-dependent photosensitizer for imaging-guided phototherapy against HeLa cancer cells at separate irradiation channels

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Correction for 'A facile strategy to realize a single/double photon excitation-dependent photosensitizer for imaging-guided phototherapy against HeLa cancer cells at separate irradiation channels' by Lin Kong et al., Chem. Commun., 2020, 56, 571-574.

The authors regret that the molecular structure of CNFBBN in the graphical abstract and Fig. 1 of the original article were incorrect. A nitrogen atom should be included in the Schiff base unit in the molecular structure of CNFBBN. The correct version of Fig. 1 is presented here.

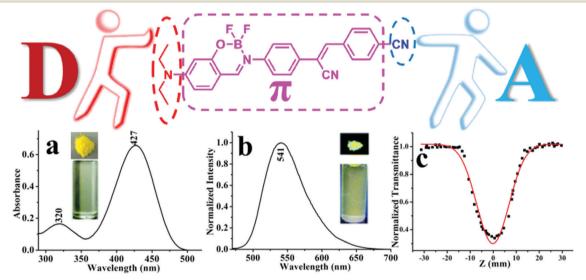


Fig. 1 Top: The structure of CNFBBN and the schematic diagram of electron-withdrawing/donating strength within it; (a) absorption spectrum in DMSO solution and (b) fluorescence spectrum in the solid state excited at 430 nm (inset: photographs under room-light and a 365 nm lamp). (c) Open Z-scan experimental result in DMSO solution under 840 nm irradiation. Solid lines show fitting to experimental data.

The Royal Society of Chemistry apologises for these errors and any consequent inconvenience to authors and readers.

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